

# DISCLOSURE OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT

**GROUP**  
**2834**

[illegible][illegible]

Lt	E	M. E. Williams et al., <i>Magnetic Levitation Scanning Stages for Extreme Ultraviolet Lithography</i> , ASPE 14 <sup>th</sup> annual meeting, Monterey CA., November 1999
Lt	F	John B. Wronosky, et al., <i>Wafer and Reticle Positioning System for the Extreme Ultraviolet Lithography Engineering Test Stand</i> , SPIE, February 2000

**EXAMINER:** Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.